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Lithographic Stochastics: Beyond 3σ (erratum)

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Equation 4 of the article [*J. Micro/Nanolithography, MEMS, and MOEMS* 16(2), 023505 (12 June 2017)] contains an error. The correct version is below. The authors wish to thank Chris Mack for pointing this out. All online versions of the article were corrected on 11 September 2017.

$$CD\,(D) = 2\sqrt{2} \cdot \tau \sqrt{\ln\,(D/D_0)} \tag{4}$$

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